



\$1756

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

Docket No: Q67319

Tsutomu SHOKI, et al.

Appln. No.: 09/987,990

Group Art Unit: 1756

Confirmation No.: 8044

Examiner: ROSASCO, STEPHEN D

Filed: November 16, 2001

For: SUBSTRATE WITH MULTILAYER FILM, REFLECTION TYPE MASK BLANK FOR EXPOSURE, REFLECTION TYPE MASK FOR EXPOSURE AND PRODUCTION METHOD THEREOF AS WELL AS PRODUCTION METHOD OF SEMICONDUCTOR DEVICE

AMENDMENT UNDER 37 C.F.R. § 1.111

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

In response to the Office Action dated July 15, 2003, please amend the above-identified application as follows on the accompanying pages.

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